

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Sang-In Lee, et al.

Serial No. **10/525,122**

Filed: **March 20, 2006**

For: **Atomic Layer Deposition of High-k
Metal Silicates**

Examiner: **Roman, Angel**

Art Unit: **2812**

Confirmation No.: **2947**

Atty. Docket No.: **067538-5171-US**

RESPONSE/AMENDMENT

Mail Stop Amendments
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed July 9, 2008, please consider the following proposed amendments to the above-identified application and the remarks herein. Accompanying this response is a Petition for extension of time with the required fee, to bring the period of response to January 9, 2009. Please amend the application as follows.

Amendments to the Claims begin on page 2 of this Amendment.

Remarks begin on page 6 of this Amendment.